



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICATION SERIAL NO 10/050,373
CONFIRMATION NO. 7531
FILING DATE January 15, 2002
INVENTORSHIP Gurtej S. Sandhu, et al.
ASSIGNEE Micron Technology, Inc.
GROUP ART UNIT 2813
EXAMINER Schillinger, Laura M.
ATTORNEY'S DOCKET NO MI22-1896
CUSTOMER NO. 021567
TITLE. Methods of Forming a Nitrogen Enriched Region

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References –See Attached Form PTO-1449

This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to ensure consideration of the references listed on the attached form PTO-1449.

The attached form PTO-1449 is submitted in compliance with 37 CFR § 1.56.

No admission is made regarding whether the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

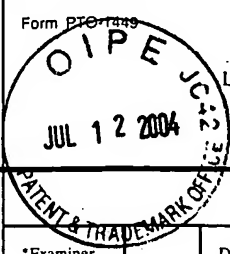
Dated: _____

7/12/04

By: _____

Robert C. Hyta
Reg. No. 46,791

EV372459911

Form PTO-1449 		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1896		SERIAL NO. 10/050,373	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Gurtej S. Sandhu et al.			
				FILING DATE January 15, 2002		GROUP 2813	

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AA	6,100,163	08/00	Jang et al.	438	437		
AB	6,399,520	06/02	Kawakami et al.	438	778		
AC							
AD							
AE							
AF							
AG							
AH							
AI							
AJ							
AK							
AL							

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AM							
AN							
AO							
AP							
AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
AR			
AS			
AT			

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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